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(71)Applicant: CJ CORP.

(72)Inventor:
 HAN, JONG GWON
 JANG, JAE YEONG
 KIM, JEONG HWAN
 KWAK, YEONG HYEON
 LEE, GWANG HO
 LEE, JAE HEUNG
 LEE, JIN HO
 OH, YUN SEOK
 PARK, JANG HUI
 SIM, JAE IK

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(54) CORYNEBACTERIUM AMMONIAGENES NV4-82-9 PRODUCING 5-XANTHYLIC ACID IN HIGHER YIELD AND PRODUCTION METHOD OF 5-XANTHYLIC ACID BY USING THE SAME

(57) Abstract:

PURPOSE: Provided are a microorganism, Corynebacterium ammoniagenes NV4-82-9, producing 5-xanthyllic acid in higher yield and having Norvaline resistance, and a production method of 5-xanthyllic acid by using the same.

CONSTITUTION: Corynebacterium ammoniagenes NV4-82-9(KFCC-11248) produces 5-xanthyllic acid(XMP) and shows Norvaline resistance.Particularly, It is characterized by growing in the presence of an infinitesimal quantity of or 6g/l of Norvaline. 5-xanthyllic acid is produced by the steps of: firstly shacking culturing Corynebacterium ammoniagenes NV4-82-9(KFCC-11248) in a seed culture medium at 30 deg.C, pH 7.3 with 180 rpm for 24 hours; secondary shacking culturing the firstly cultured Corynebacterium ammoniagenes NV4-82-9(KFCC-11248) in a seed culture medium at 31 deg.C, pH 7.3 with 900 rpm for 24 hours to activate it; and shacking culturing the secondary cultured Corynebacterium ammoniagenes NV4-82-9(KFCC-11248) at 33 deg.C with 400 rpm for 90 hours in a fermentation medium, wherein if the content of sugar remaining in the culture solution is 1% or less, glucose can be added in the amount to reach total sugar content of 30%.

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